

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	1	("2854447").PN.	US-PGPUB; USPAT	OR	OFF	2006/09/15 11:33
L2	1	("2854477").PN.	US-PGPUB; USPAT	OR	OFF	2006/09/15 11:33
S1	1	("5543268").PN.	US-PGPUB; USPAT	OR	OFF	2006/09/14 08:40
S2	1	("5985525").PN.	US-PGPUB; USPAT	OR	OFF	2006/09/14 09:09
S3	1	("5300404").PN.	US-PGPUB; USPAT	OR	OFF	2006/09/14 09:21
S4	1	("6329126").PN.	US-PGPUB; USPAT	OR	OFF	2006/09/14 12:45
S5	1242	diphenylethersulfonate or diphenylethersulfonic or (diphenylether adj sulfonate) or (diphenylether adj sulfonic) or (diphenyl adj ether adj sulfonate) or (diphenyl adj ether adj sulfonic) or (diphenylether adj disulfonate) or (diphenylether adj disulfonic) or (diphenyl adj ether adj disulfonate) or (diphenyl adj ether adj disulfonic)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/15 09:21
S6	135466	(resist or photoresist or photopolymer or lithograph\$) same (develop or developing or developer or developed or development)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/14 13:12
S7	68	S5 and S6	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/15 09:24
S8	214	diphenylethersulfonate or diphenylethersulfonic or ((diphenylether adj sulfonate) or (diphenylether adj sulfonic) or (diphenyl adj ether adj sulfonate) or (diphenyl adj ether adj sulfonic) or (diphenylether adj disulfonate) or (diphenylether adj disulfonic) or (diphenyl adj ether adj disulfonate) or (diphenyl adj ether adj disulfonic)) same (formula or structure)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/15 09:23

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S9	1242	diphenylethersulfonate or diphenylethersulfonic or (diphenylether adj sulfonate) or (diphenylether adj sulfonic) or (diphenyl adj ether adj sulfonate) or (diphenyl adj ether adj sulfonic) or (diphenylether adj disulfonate) or (diphenylether adj disulfonic) or (diphenyl adj ether adj disulfonate) or (diphenyl adj ether adj disulfonic)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/15 09:24
S10	135466	(resist or photoresist or photopolymer or lithograph\$) same (develop or developing or developer or developed or development)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/15 09:24
S11	68	S9 and S10	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/15 09:24
S12	201	S8 not S11	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/15 11:27